

RIBER

Press release – Rusnanoprize
Bezons, France, July 27, 2009; 17.45 PM

RIBER awarded the Rusnanoprize by the Russian Nanotechnology Society

Bezons, France, July 27, 2009 – 17.45 pm– RIBER, the global leader for molecular beam epitaxy (MBE), announces that it will be awarded the “Rusnanoprize” by the Russian Nanotechnology Society at a ceremony due to take place in Moscow on October 6 next. This prestigious prize will be awarded in recognition of the implementation of the MBE technology within the semi-conductor industry.

Created by the Russian Nanotechnology Society, the “Rusnanoprize” international prize objective is to promote innovation in the fields of NanoElectronics, NanoMaterials, NanoBiotechnology and NanoDiagnostics. It is awarded each year to major scientific and technological developments and their application to industrial manufacturing.

The 2009 Prize will be first awarded to the Russian Leonid Keldych and to the American Alfred Y. Cho, both researchers having made significant contributions in the development of the molecular beam epitaxy process and its application, As well as this award, RIBER will receive a prize for having introduced the first commercial molecular beam epitaxy equipment in the world in the late 70's and having enabled it from research to production:-

This award demonstrates that RIBER is a major nanotechnology player capitalizing on a significant technological expertise and enjoying a tremendous reputation within the scientific community as well as the manufacturers of compound semi-conductor based devices.

While molecular beam epitaxy is a nanostructure growth process used in most advanced research in the field of electronic, photonic, or sensing, it is also used in the manufacture of ultra-rapid electronic devices found in cell phones and nomadic devices, optic fiber communication networks, radars, telecom satellites, cable television, as well as lasers found in optic fiber networks, sensor, medical instruments, cutting machinery, CD players, etc..

The MBE equipments developed by RIBER provide numerous advantages to its users:

- Very high quality of crystal materials as well as outstanding nano-layers uniformities allowing breakthrough advances in research;
- Significant productivity gains due to a high substrate processing capacity, time required for epitaxy, and lastly, a high activity time.
- A significant reduction in operating costs, in particular due high efficiency process and reduced maintenance costs.

The quality of the award-winning work thus rewards RIBER's ambitious policy in terms of applied research to test new products or new procedures, such as new molecular beam deposition techniques. It testifies to Riber's unrelenting commitment to major R&D programs and close cooperation with the main international research centers. lastly, it is the result of long-standing technical partnerships with MBE technology users in Russia.

The formal prize-giving ceremony of the “Rusnanoprize” will take place at the Moscow International Nanotechnology Forum, from October 6 to 8, 2009.

About RIBER:

Riber designs and produces molecular beam epitaxy (MBE) systems as well as evaporation sources and cells for the semi-conductor industry. This high-technology equipment is essential for the manufacture of compound semi-conductor materials and new materials that are used in numerous consumer applications such as new Information Technologies, OLED flat screens and the new generation of solar cells.

Riber SA's shares are listed in Compartment "C" of the Euronext Paris Stock Exchange and are a component of the CAC IT index.

ISIN Code: FR0000075954

Reuters Code: RIBE.PA

Bloomberg Code: RIB.FP

Riber has been awarded the OSEO innovation certification, enabling it to qualify for FCPIs (French mutual funds).

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